EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S96	129	heat near2 treat\$4 near10 temperature near10 (ramp\$4 or rate) same (si or silicon) near5 (single near2 crystal\$5 or wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR-	ON	2006/02/26 16:33
L1	136	heat near2 treat\$4 near10 temperature near10 (ramp\$4 or rate) same (si or silicon) near5 (single near2 crystal\$5 or wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 16:33
S87	184	wafer and (anneal\$3 or (heat adj treat\$4) or (rapid adj thermal) or RTA or RTP or PTP) same temperature and czochralski and (oxygen or O2) and (oSF or OSIF or BMD or (oxide adj induced))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	.OR	ON	2006/02/26 16:34
L2	222	wafer and (anneal\$3 or (heat adj treat\$4) or (rapid adj thermal) or RTA or RTP or PTP) same temperature and czochralski and (oxygen or O2) and (oSF or OSIF or BMD or (oxide adj induced))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 16:34
S1	585	(kozo near2 nakamura or toshiaki near2 saishoji or hirotaka near2 nakajima or masashi near2 nishimura or toshirou near2 kotooka near2 yoshiyuki near2 shimanuki).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 16:49
L4	43	3 and heat near2 treat\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 16:49
L3	658	(kozo near2 nakamura or toshiaki near2 saishoji or hirotaka near2 nakajima or masashi near2 nishimura or toshirou near2 kotooka near2 yoshiyuki near2 shimanuki).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 16:49
S49	95	(anneal\$ or heat\$3 near2 treat\$4 or rta or rtp or ptp) same (Si or silicon) near4 wafer same (heat\$4 or ramp\$4) near2 rate same temperature	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR ·	ON	2006/02/26 16:50
L5	138	(anneal\$ or heat\$3 near2 treat\$4 or rta or rtp or ptp) same (Si or silicon) near4 wafer same (heat\$4 or ramp\$4) near2 rate same temperature	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/26 16:50